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DATE June 26, 2001

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JUN 26 2001

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## COMMENTS:

**URGENT**

I have attached an informal communication in regard to the above-referenced matter.

Please give me a call if you have any questions.

Thank you,  
Edwin S. Flores, Ph.D., J.D.

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**URGENT COMMUNICATION****IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of: Harold R. Garner  
Serial No: 09/326,526  
Filing Date: June 4, 1999  
Group/Art Unit: 2872  
Examiner: Phan, J.  
Title: DIGITAL OPTICAL CHEMISTRY MICROMIRROR IMAGER

**VIA FACSIMILE (703) 308-7722****INFORMAL COMMUNICATION**

Proposed Amendment to the claims:

Cancel claims 2, 4-7.

Amend claim 1 with the limitation of claim 7.

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1. An apparatus for catalyzing a reaction on a substrate comprising:
  - a light source;
  - a diffusion lens between said light source and said micromirror
  - a micromirror positioned to redirect light from said light source toward said substrate;
  - a computer connected to, and controlling, said micromirror; and
  - a reaction chamber is placed in the path of light redirected by said micromirror, wherein light that is redirected by said micromirror catalyzes a chemical reaction proximate said substrate in said reaction chamber.
8. The apparatus of claim 1 wherein said light interacts with a novolak resin proximate said substrate to produce a photoresist pattern.
13. The apparatus of claim 1 further comprising:
  - a reaction chamber disposed about said substrate;

one or more reactant lines connected to said reaction chamber;  
one or more reaction chemicals connected to said reactant lines; and  
a computer connected to, and controlling, the supply of said one or more reaction chemicals to said reaction chamber via said reactant lines.

14. The apparatus of claim 13 wherein said one or more of said reaction chemicals is involved in a chemical reaction when exposed to light.
15. An apparatus for catalyzing a reaction on a substrate comprising:  
a light source;  
a micromirror positioned to redirect light from said light source toward said substrate;  
a reaction chamber disposed about said substrate;  
one or more reactant lines connected to said reaction chamber;  
one or more reaction chemicals connected to said reactant lines; and  
a computer connected to, and controlling, said micromirror and the supply of said one or more reaction chemicals to said reaction chamber via said reactant lines, wherein a light catalyzable reaction occurs proximate to the site where light produced by said light source and redirected by said micromirror strikes said substrate.
16. The apparatus of claim 15 wherein said light source is a UV light.
18. The apparatus of claim 15 wherein said light source is a xenon lamp, or a mercury lamp, or a laser or a combination thereof.

19. The apparatus of claim 15 further a lens system comprising:  
a diffusion lens between said light source and said micromirror; and  
a lens between said micromirror and said substrate.
20. The apparatus of claim 15 wherein said micromirror is further defined as a micromirror array.
21. The apparatus of claim 15 wherein said light interacts with a novolak resin proximate said substrate to produce a photoresist pattern.
26. The apparatus of claim 15 further comprising a total internal reflection mirror disposed in a position to redirect light from said light source into said micromirror and from said micromirror array toward said substrate.
27. The apparatus of claim 15 wherein said substrate is mounted on a movable platform that can be controlled via a computer to allow for multiple repetitive exposures of said substrate to light reflected by said micromirror.